

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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## Title of Invention

A METHOD FOR SUPERCRITICAL CARBON DIOXIDE  
PROCESSING OF FLUORO-CARBON FILMS

Application Number : 10/711649



Confirmation Number: 5648

First Named Applicant: Kohei Kawamura

Attorney Docket Number: SSIT-114

Art Unit: 1756

Examiner:

Search string: ( 6485895 or 6486078 or 6492090 or 6500605 or 6508259 or 6509136 or 6521466 or 6537916 or 6541278 or 6546946 or 6550484 or 6635582 or 6641678 or 6656666 or 6669916 or 6673521 or 6677244 or 6685903 or 6737725 or 6764552 or 6777312 or 6780765 ).pn

## US Patent Documents

**Note: Applicant is not required to submit a paper copy of cited US Patent Documents**

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	6485895	2002-11-26	Choi et al.	B1	430	330
	2	6486078	2002-11-26	Rangarajan et al.	B1	438	778
	3	6492090	2002-12-10	Nishi et al.	B2	430	270.1
	4	6500605	2002-12-31	Mullee et al.	B1	430	329
	5	6508259	2003-01-21	Tseronis et al.	B1	134	105
	6	6509136	2003-01-21	Goldfarb et al.	B1	430	272.1
	7	6521466	2003-02-18	Castrucci	B1	438	5
	8	6537916	2003-03-25	Mullee et al.	B2	438	692
	9	6541278	2003-04-01	Morita et al.	B2	438	3
	10	6546946	2003-04-15	Dunmire	B2	137	15.18
	11	6550484	2003-04-22	Gopinath et al.	B1	134	1.2
	12	6635582	2003-10-21	Yun et al.	B2	438	745
	13	6641678	2003-11-04	DeYoung et al.	B2	134	36
	14	6656666	2003-12-02	Simons et al.	B2	430	322
	15	6669916	2003-12-30	Heim et al.	B2	423	245.1
	16	6673521	2004-01-06	Moreau et al.	B2	430	315
	17	6677244	2004-01-13	Ono et al.	B2	438	706
	18	6685903	2004-02-03	Wong et al.	B2	423	262
	19	6737725	2004-05-18	Grill et al.	B2	257	522
	20	6764552	2004-07-20	Joyce et al.	B1	134	3
	21	6777312	2004-08-17	Yang et al.	B2	438	464

**Remarks**

Note: Remarks are not for responding to an office action.

In accordance with the duty of candor and good faith imposed by 37 CFR 1.56 and means of complying therewith according to 37 CFR 1.97 and 1.98, the references listed in this Supplemental Information Disclosure Statement are called to the attention of the United States Patent and Trademark Office in connection with the above-identified patent application. No admission is made that the cited art represents the prior art or that the cited art is the most material art. In accordance with 37 CFR 1.97(b), this Supplemental Information Disclosure Statement shall be considered because it is filed before the mailing date of a first Office Action on the merits. The Examiner is urged to consider all the cited references and to make an independent decision with respect to their materiality. Applicants believe no fee is due in connection with the filing of this paper. If any additional fees are necessary to complete this communication, please apply them to Deposit Account No. 23-3000.

**Signature**

Examiner Name	Date